Universal Small Polaron Formation in Chemically Doped MoS₂ Mediates Impurity-Assisted Conduction

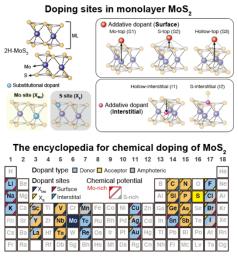
Soungmin Bae1

Institute for Materials Research, Tohoku University, Japan

Two-dimensional transition metal dichalcogenides (TMDs) are increasingly becoming the focus of research due to their promising applications in advanced electronics. Modifying the electrical and magnetic characteristics of TMDs via doping is crucial for enhancing the performance of TMD-based devices significantly.

Various experimental approaches to elemental doping are sought after for improving the durability and stability of TMDs. These methods enable a variety of doping configurations, encompassing substitutional dopants, surface adsorption, and lattice

interstitials. In our comprehensive study, we explored the thermal stability and electrical dopability of 27 different types of acceptor and donor dopants in monolayer MoS₂, employing a self-interaction free Koopmans' compliant functional from first principles.[1] Our findings reveal universal small polaronic formations across a broad spectrum of dopants, even valid for the bulk MoS₂. This implies that the impurity hopping mechanism should be predominant for electric carrier conduction in chemically doped TMDs. Our work provides a foundational theoretical background of the chemical doping of TMDs for practical applications.



References

1. <u>S. Bae</u>*, I. Miyamoto, S. Kiyohara, and Y. Kumagai*, *ACS Nano* 18, 50, 33988– 33997 (2024). <u>https://doi.org/10.1021/acsnano.4c08366</u>